

Notice of References Cited	Application/Control No. 10/605,977	Applicant(s)/Patent Under Reexamination RINERSON ET AL.	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-5,280,013	01-1994	Newman et al.	505/330
	C	US-6,569,745 B2	05-2003	Hsu, Sheng Teng	438/385
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NON-PATENT DOCUMENTS

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	U	Wolf, Ph.D., Stanley, Richard N. Tauber, Ph.D., "Aluminum Thin Films and Physical Vapor Deposition in VLSI," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, pp. 335, 367.
	V	Wolf, Ph.D., Stanley, "Contact Technology and Local Interconnects for VLSI," Silicon Processing for the VLSI Era - Vol. 2: Process Integration, Lattice Press, 1986, pp. 121-123.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.